



**PATENT APPLICATION**

**RESPONSE UNDER 37 CFR §1.116  
EXPEDITED PROCEDURE  
TECHNOLOGY CENTER ART UNIT 2826**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**In re the Application of**

**Akira SAKAI et al.**

**Group Art Unit: 2826**

**Application No.: 10/807,235**

**Examiner: E. PERT**

**Filed: March 24, 2004**

**Docket No.: 119232**

**For: METHOD FOR FABRICATING A METALLIC OXIDE OF HIGH DIELECTRIC CONSTANT, METALLIC OXIDE OF HIGH DIELECTRIC CONSTANT, GATE INSULATING FILM AND SEMICONDUCTOR ELEMENT**

**AMENDMENT AFTER FINAL REJECTION UNDER 37 CFR §1.116**

**Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450**

*Please enter  
11/3/05*

**Sir:**

**In reply to the May 23, 2005 Office Action, please consider the following:**

**Amendments to the Claims as reflected in the listing of claims; and**

**Remarks.**